

EUV Photoresist Sensitivity Calibrations

	Esize (mJ/cm ²)		Ratio
	New	Old	
MET 1K	13.6	25	1.84
P1123	10.2	25	2.45

Absolute resist calibration measurements done using the CXRO Calibrations and Standards Beamline and the CXRO EUV Microfield Exposure Tool have revealed that EUV resist are twice as fast as previously thought. These results apply to essentially all EUV photoresist and all EUV tools in the world.
